

Photosensitive material for immersion photolithography

ABSTRACT OF THE INVENTION

When rays of light converge inside a photosensitive material at angles larger than 70 degrees, one polarization of the light may fail to produce the desired image contrast in conventional exposure media. This invention describes means of suppressing the effects of the undesired polarization by using a class of photosensitive media that are insensitive to that polarization and more sensitive to the polarization conveying the desired image contrast as well as by means of optical configurations relevant in the context of semiconductor manufacturing using photolithography.